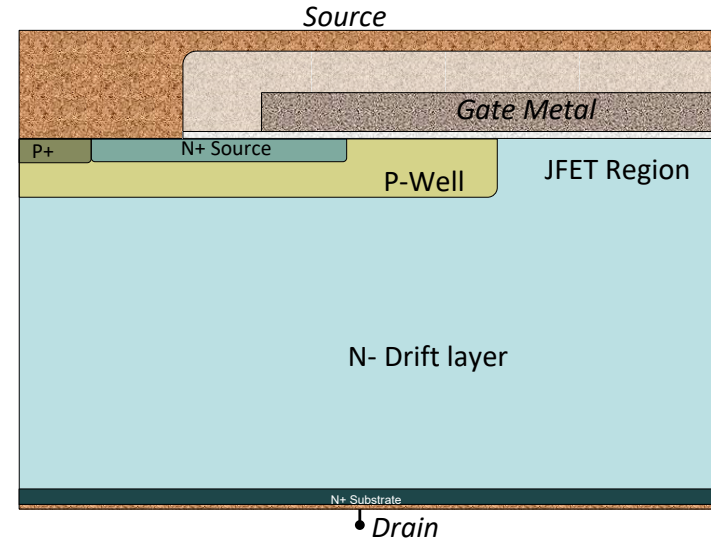


# Avalanche and Short-Circuit Robustness of High Voltage SiC DMOSFETs

Ranbir Singh, Siddarth Sundaresan  
GeneSiC Semiconductor Inc.

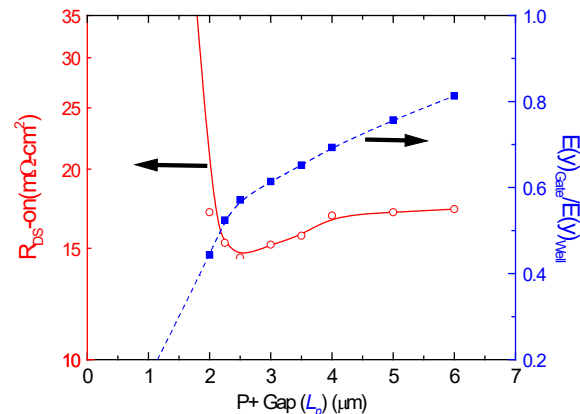
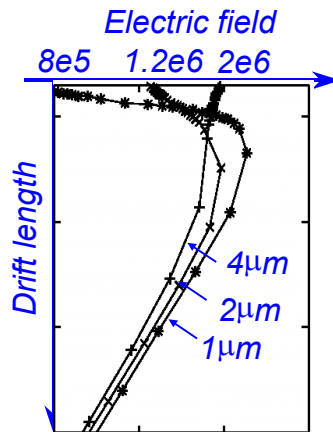
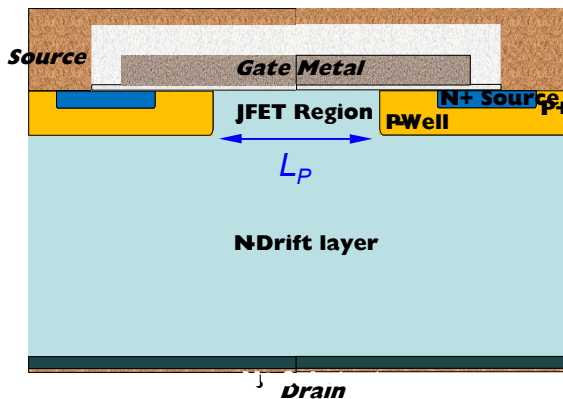
# SiC MOSFET Design Considerations

- **Low Drain-Source Resistance,  $R_{DS,on}$**
- **Low Gate Charge, Input and Output Capacitances**
- **Robust Design for High Avalanche Ruggedness**
- **Low conduction loss at high temperatures**
- **Intrinsic diode with low reverse recovery charge**
- **Low Costs at high**

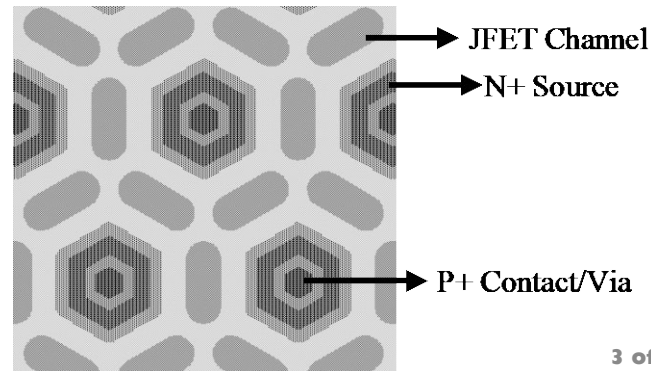


**Standard DMOSFETs for highly uniform production and robust and reliable performance**

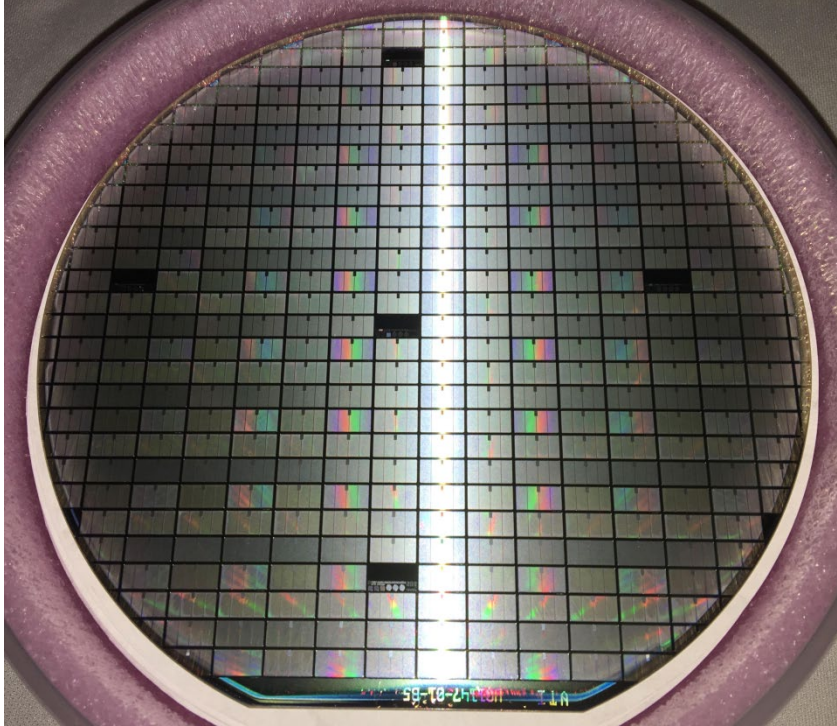
# Due to low channel mobility, MOSFET design points are constrained



- **Small Channel Length => Needs low Electric Field at Oxide => Smaller JFET Length => High Rdson**
- **Under Short Circuit conditions, High Electric Field at Oxides Observed**
- **Different Layout schemes can be employed to trade-off Rdson/Short Circuit/Avalanche parameters**

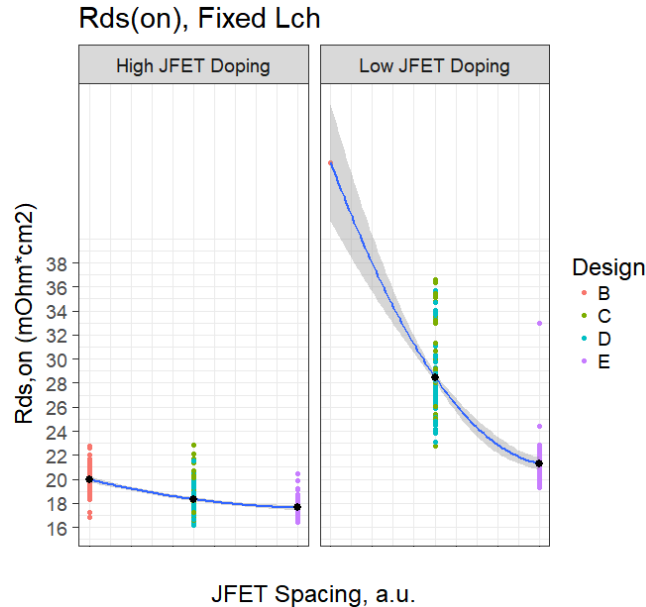


# Leading 4000 V/40 m $\Omega$ MOSFETs produced

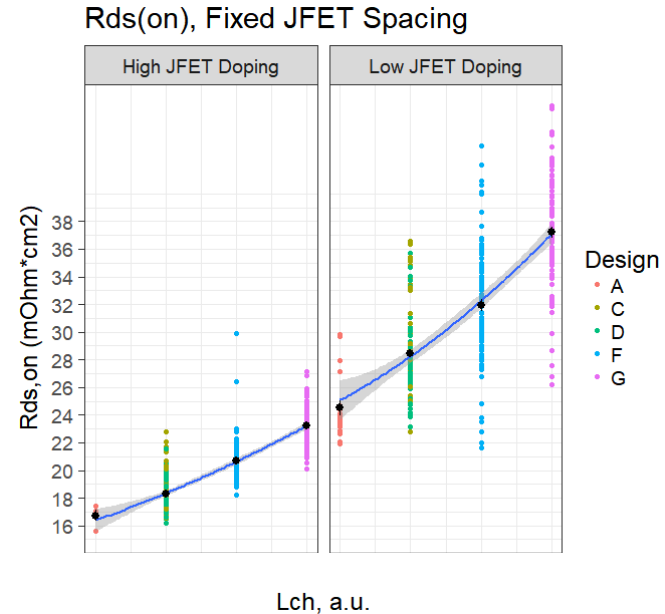


- **4000 V/40 m $\Omega$  MOSFETs fabricated on 150 mm wafers**
- **Chip Size = 8.9 mm x 4.82 mm**

# $R_{DS,ON}$ for various designs

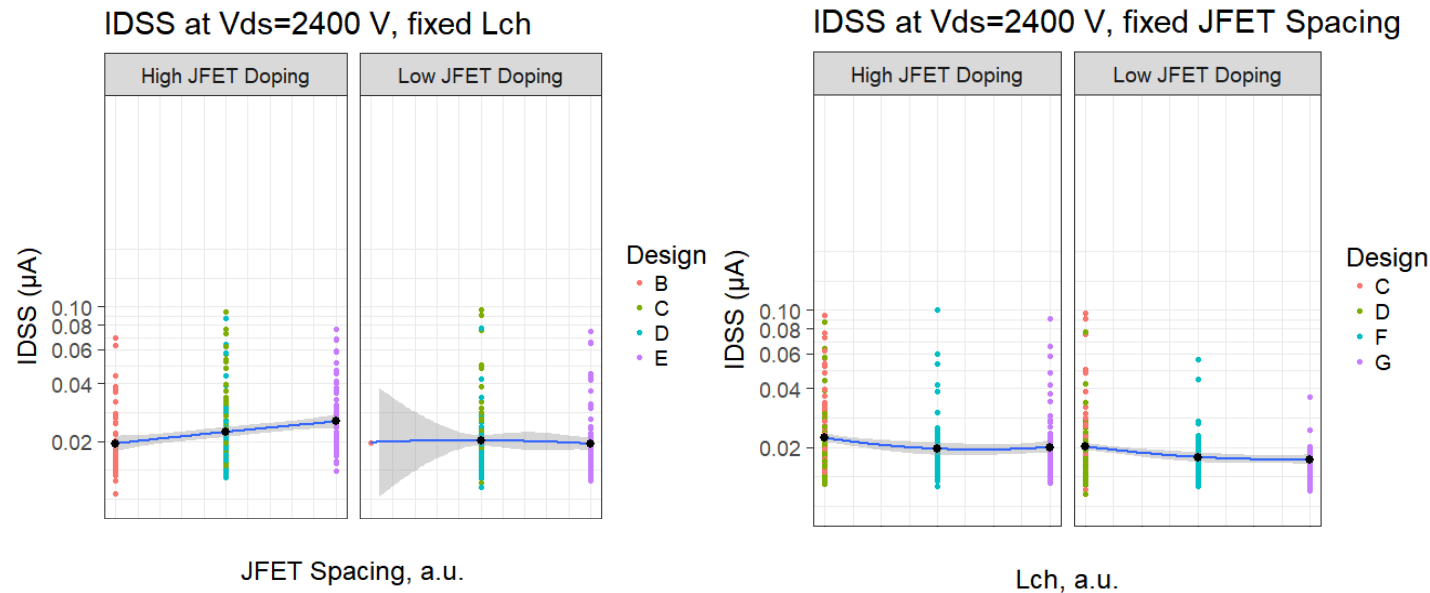


- $R_{DS,ON}$  reduces with increasing JFET spacing
- Higher JFET doping has clear impact in reducing  $R_{DS,ON}$



- $R_{DS,ON}$  increases with increasing  $L_{ch}$
- Higher variation in  $R_{DS,ON}$  observed in devices with low JFET doping

# Leakage current ( $I_{DSS}$ ) for various device designs

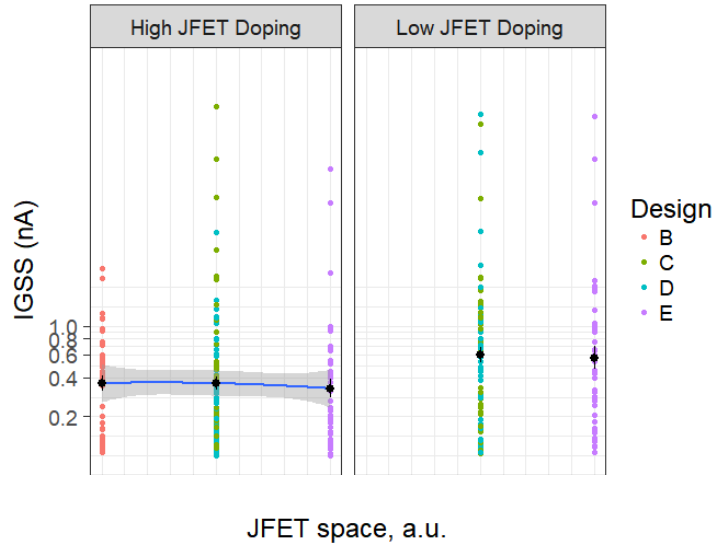


- **No significant impact of JFET Doping on  $IDSS$**
- **Median  $IDSS$  is higher for wider JFET spacing, for devices with higher JFET doping**

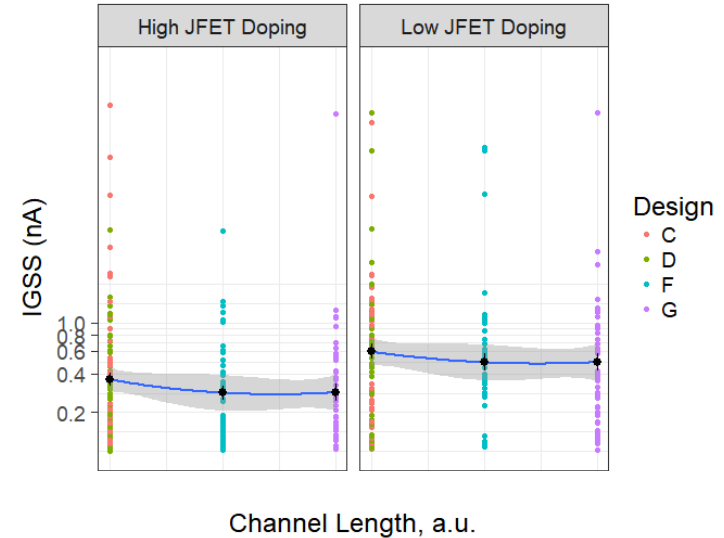
- **Median  $IDSS$  values are  $< 30$  nA at  $V_{DS} = 2400$  V**
- **No significant impact of  $L_{CH}$  on  $I_{DSS}$**

# Gate leakage current ( $I_{GSS}$ ) for various device designs

$I_{GSS}$  at  $V_g = 20$  V, Fixed  $L_{ch}$



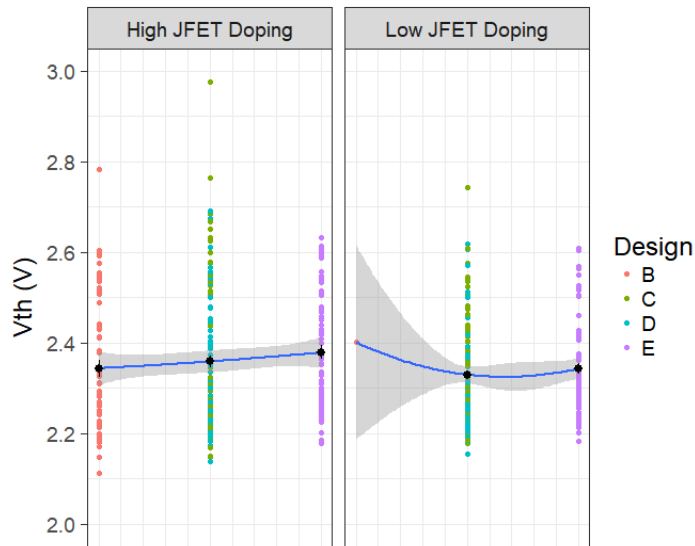
$I_{GSS}$  at  $V_g = 20$  V, fixed JFET spacing



- **Median  $I_{GSS}$  values  $< 1$  nA for all designs**
- **No impact of JFET doping on gate leakage current**
- **Very slight statistical decrease of  $I_{GSS}$  observed for longer channel DMOSFETs**

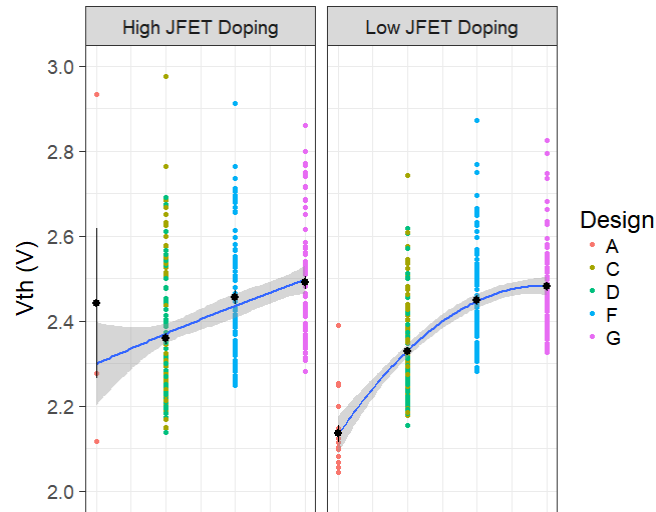
# Threshold Voltage ( $V_{TH}$ ) for different device designs

$V_{th}$  at  $I_d = 5$  mA, Fixed Lch



JFET space, a.u.

$V_{th}$  at  $I_d = 5$  mA, Fixed JFET Spacing



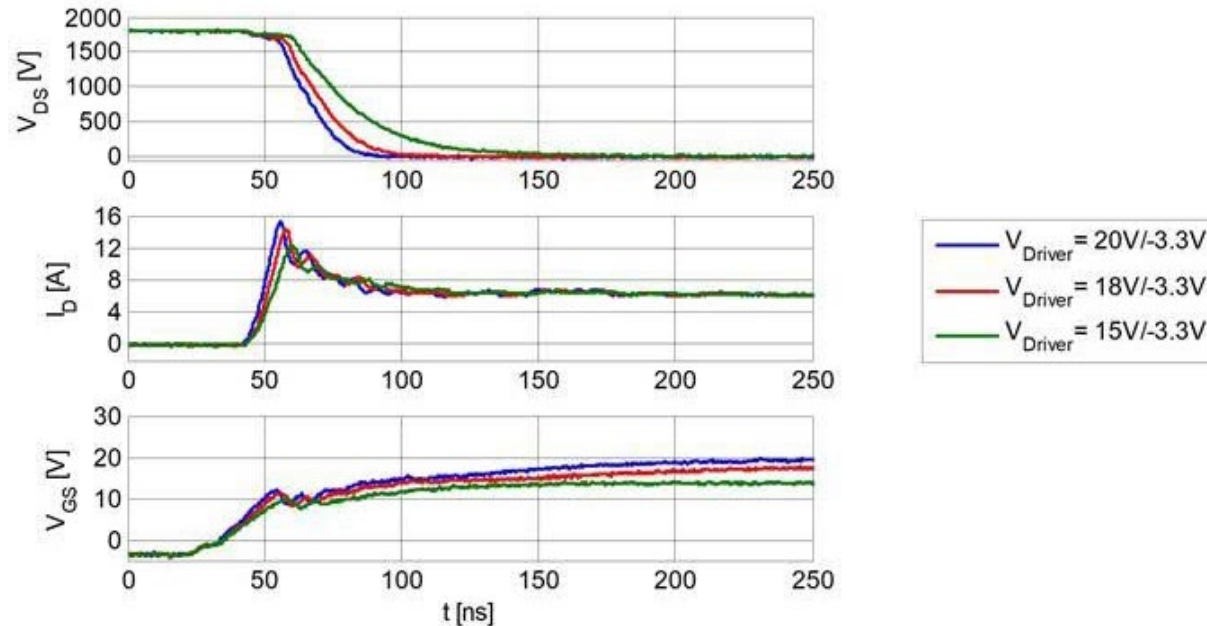
Channel Length, a.u.

- **No impact of JFET Doping on  $V_{th}$**
- **$V_{th}$  is only weakly dependent on the JFET Spacing**

- **Clear dependence of  $V_{th}$  on MOS channel length is observed**
- **$V_{th}$  reduction at lower channel lengths is due to the DIBL effect**

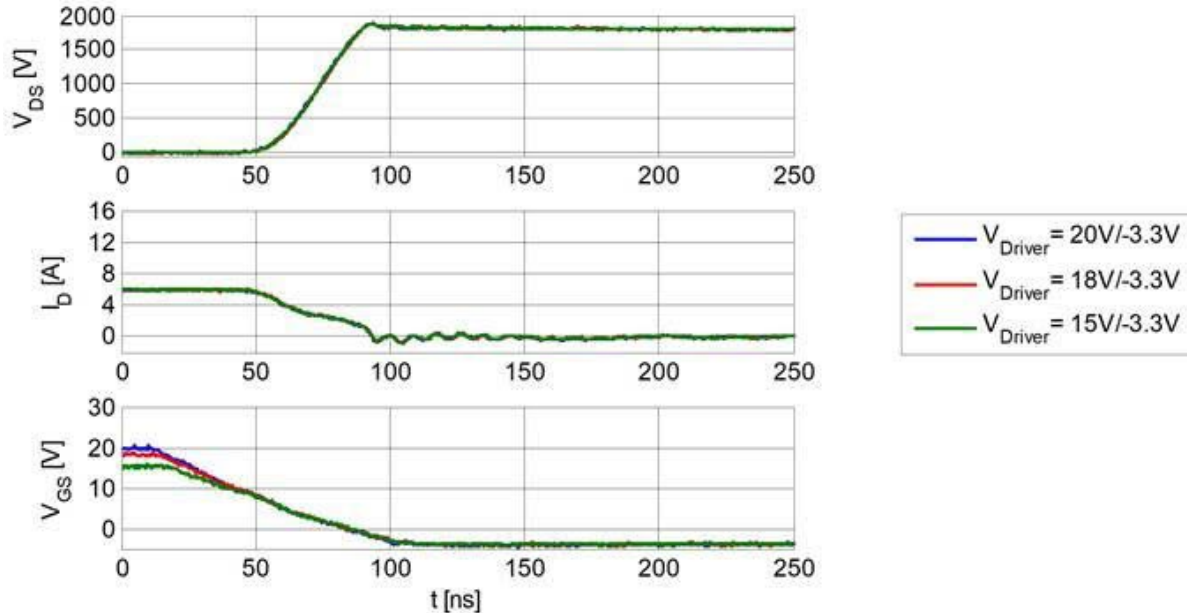


# Double Pulse switching characterization



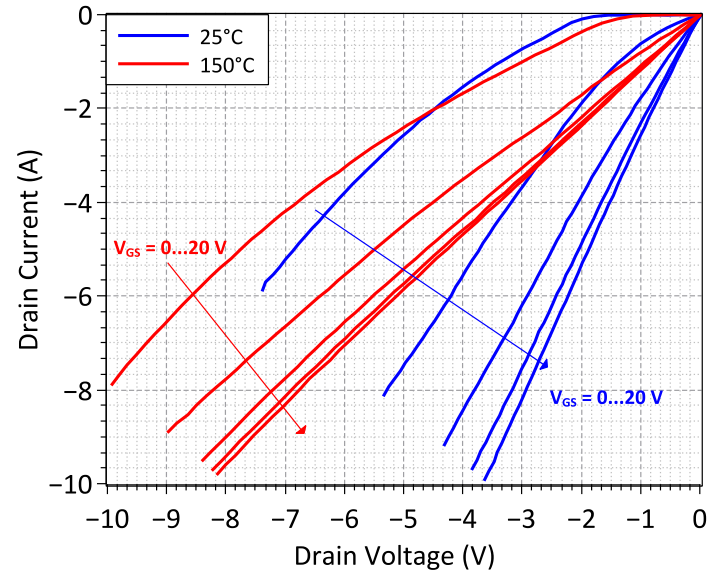
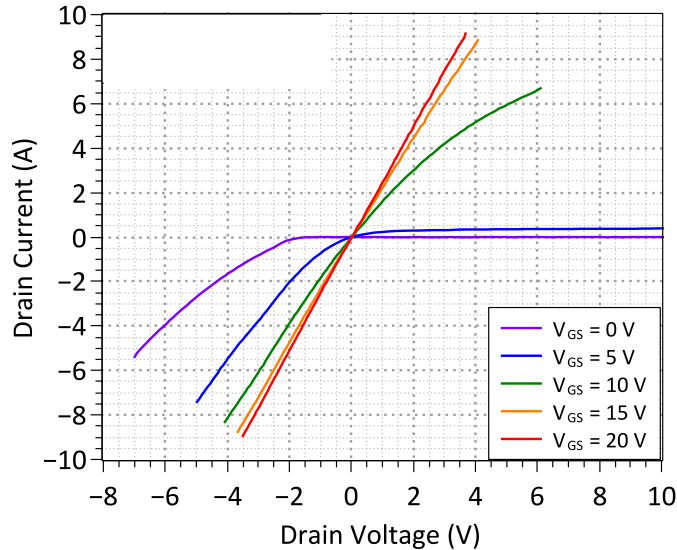
- **$V_{DS}$  fall time = 30 ns achieved for switching at 1800 V and 6 A, with +20 V drive voltage and  $R_{G,ext} = 10 \Omega$**

# Double Pulse switching characterization



- **VDS rise time = 30 ns achieved for switching at 1800 V and 6 A, with -3.3 V Gate Drive Voltage**

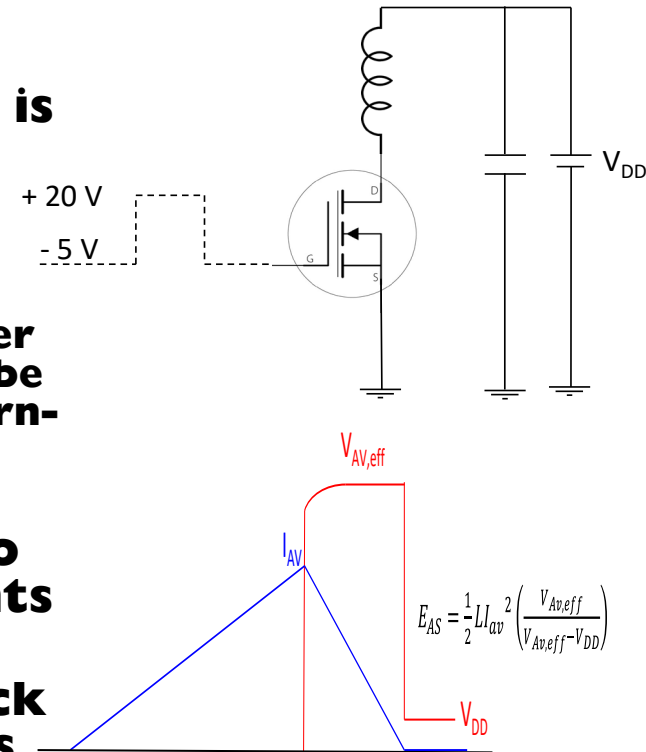
# Negative Drain bias characteristics



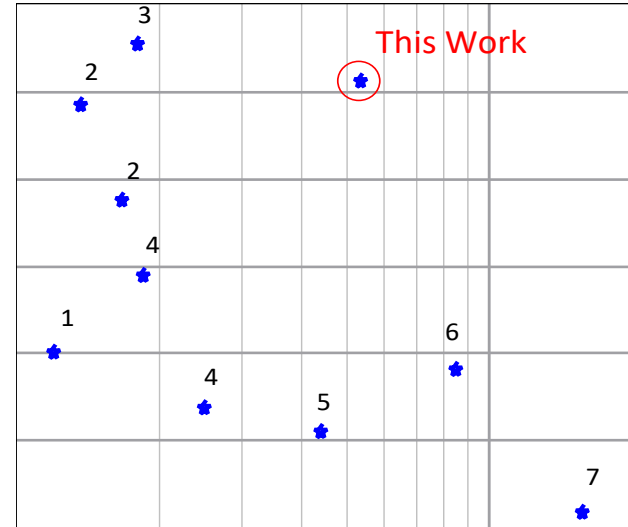
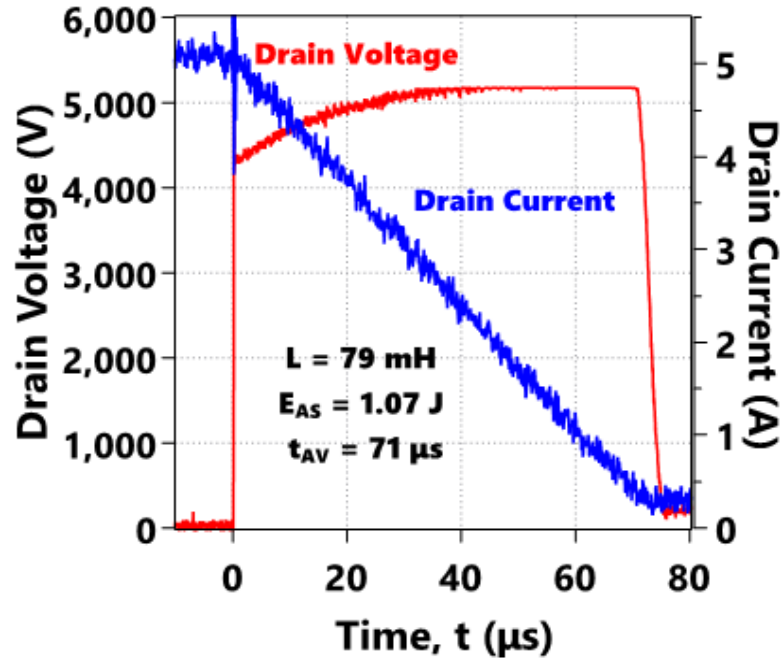
- **The negative drain bias (synchronous rectifier mode) performance of the DMOSFET at 25°C and 150°C is shown**
- **Depending on the magnitude of the gate bias and the junction temperature, the device operates in either purely bipolar mode, purely unipolar mode, or in a mixed-mode.**

# Avalanche robustness of 4600 V DMOSFETs

- **Short-Circuit and Unclamped Inductive Switching (UIS)** tests are widely used to define the SOA limits of power devices
- **Avalanche ruggedness of a power device is determined by its ability to dissipate avalanche energy (EAV) without catastrophic device failure**
  - Both single-pulse and repetitive avalanche ratings are important for ultra-fast SiC power MOSFETs, since high voltage overshoots can be generated due to high  $di/dt$  during device turn-off
- **An avalanche rugged device enables snubber-less converter design, leading to drastic reduction in cost, # of components and converter size**
- **Automotive applications such as anti-lock braking systems and engine control units require power devices to dissipate more**

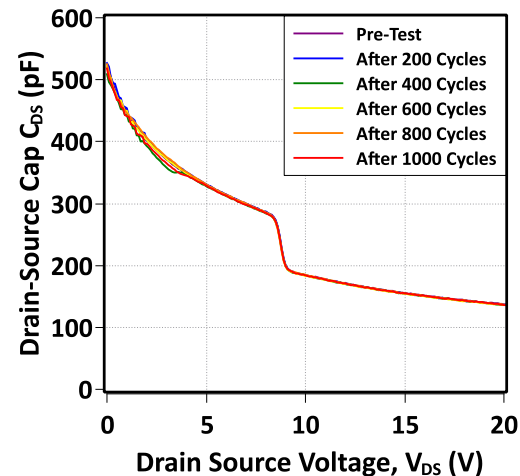
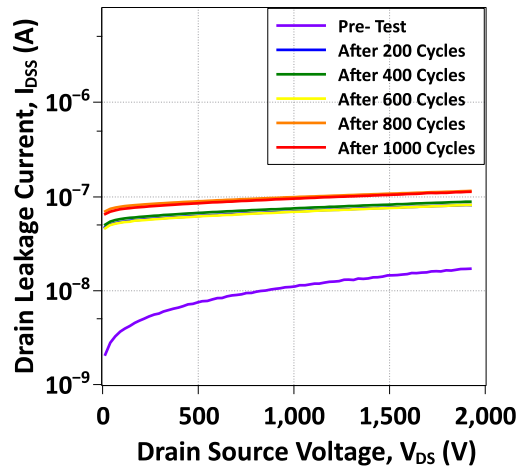
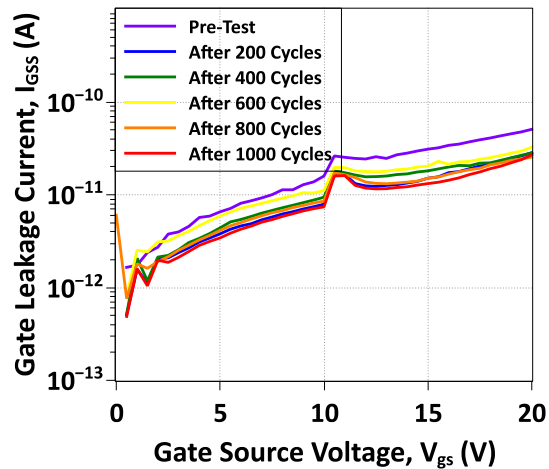


# Single pulse avalanche energy



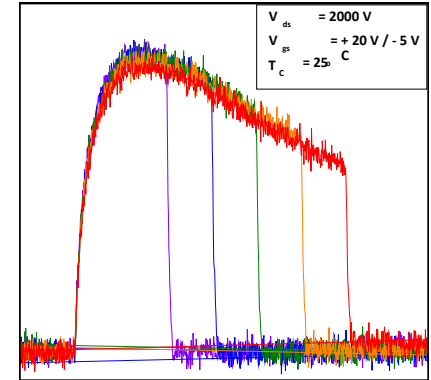
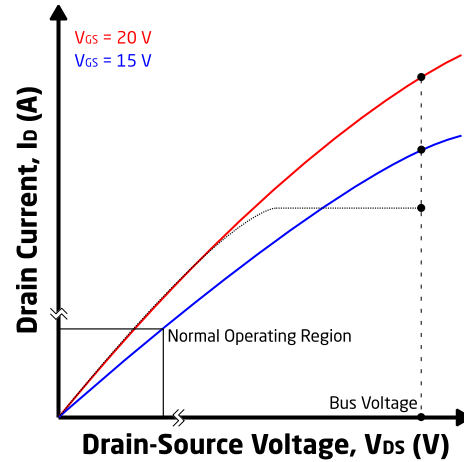
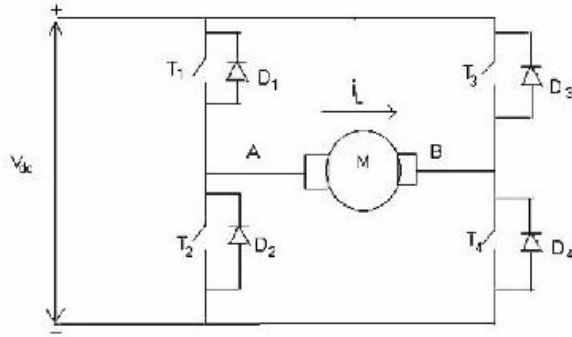
- **SiC MOSFET successfully conducts a single-pulse avalanche energy (EAS) of 1.07 J (14.1  $\text{J}/\text{cm}^2$  normalized to the total chip size), at a peak drain current of 5.5 A, and drain voltage of 5100 V.**
- **An EAS of 14.1  $\text{J}/\text{cm}^2$  is among the highest ever recorded for a SiC MOSFET.**

# Stability of electrical characteristics after repetitive avalanche stress



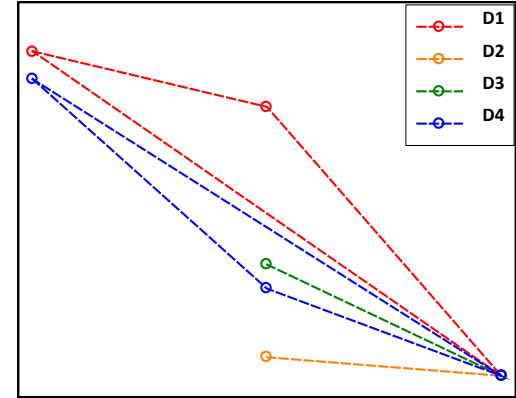
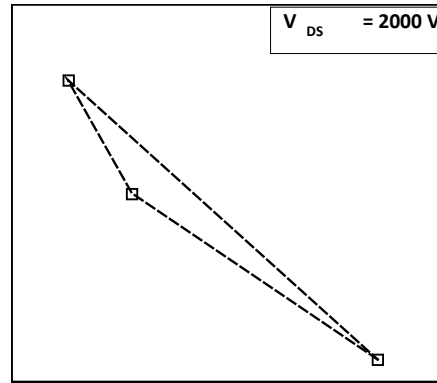
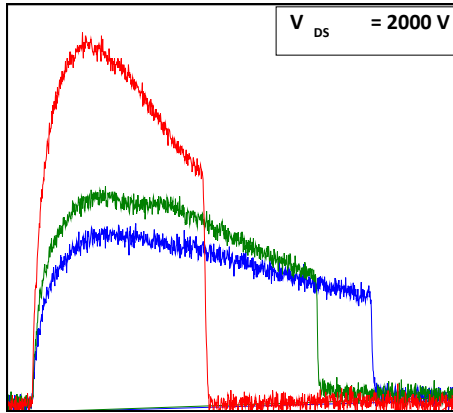
- **200 mJ, 1000 cycle repetitive Avalanche Tests**
- **Minor degradation of Drain Leakage current**
- **No degradation (not shown) of output, transfer and body diode characteristics as well**

# Short-Circuit analysis



- **Many Applications demand Short circuit capability - for certain period of time ( $5\text{-}10\mu\text{sec}$ ), the MOSFET should survive application of BUS voltage at near-full current**
- **Particularly challenging for SiC MOSFETs because short-channel makes output conductance poor (Saturation current increases with Drain Bias)**
- **Sophisticated behavioral models developed by GeneSiC to estimate energy deposited into the device for various short circuit times**

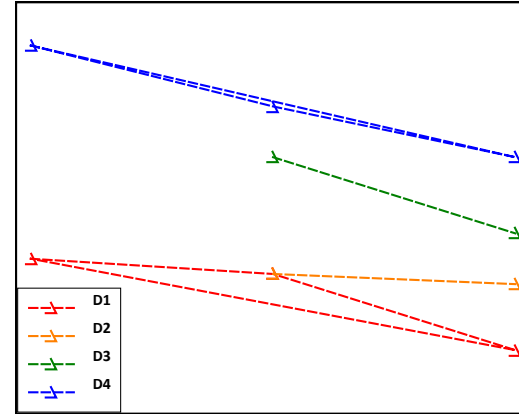
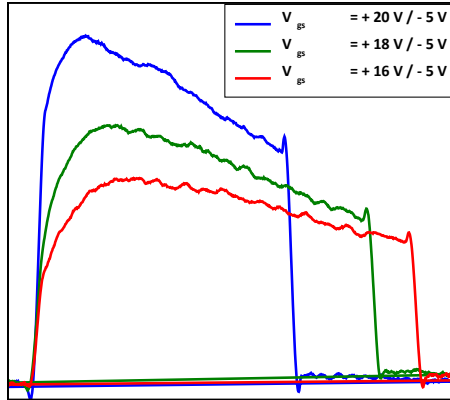
# Impact of channel length and JFET parameters on short circuit times



- **Increasing Channel length, and other parameters improves Saturation characteristics of MOSFET, which limits Drain Current and hence longer T<sub>sc</sub>**
- **However, RDS penalty ensues**

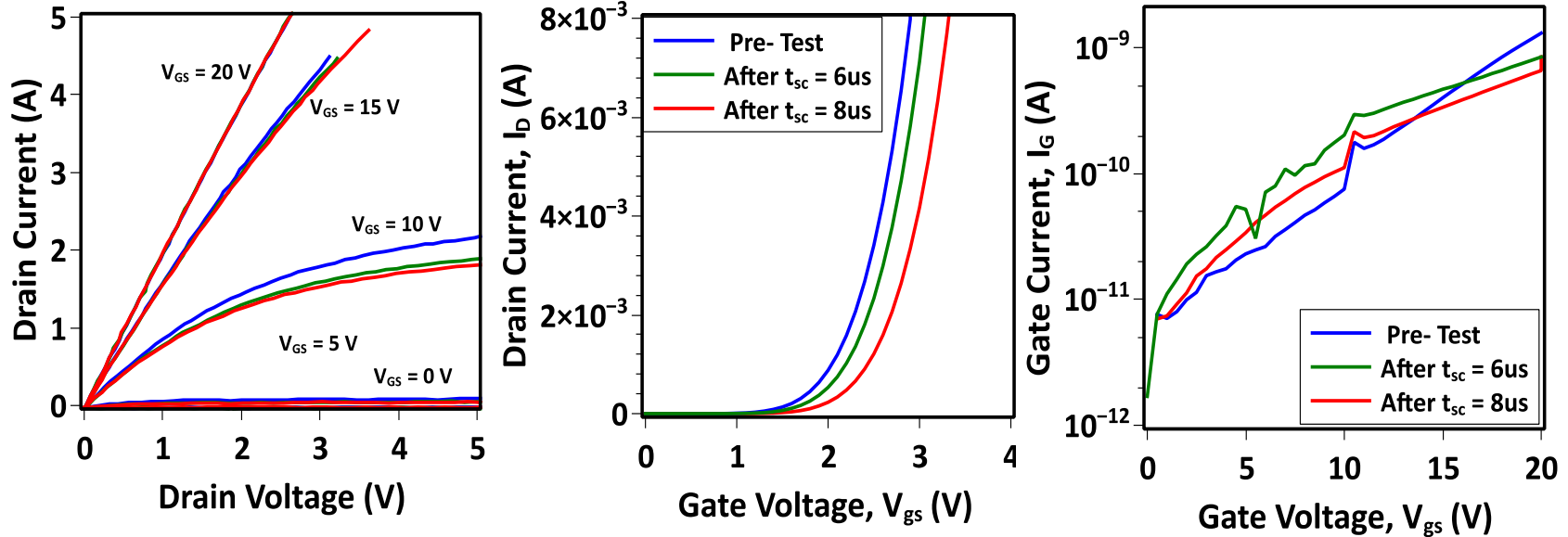


# Impact of gate bias on short circuit failure






- **A good solution is limiting the Gate Drive Voltage to 15 or 16V instead of 20V**
- **Short Circuit Times can be enhanced by reduced Gate Biases**

# Impact of short circuit on device characteristics



- **Not much degradation of MOSFETs after short circuit pulses applied**
- **1000 cycle tests of 6usec pulses show no significant degradation of MOSFET characteristics (not shown)**

# GeneSiC's SiC MOSFET Roadmap

Rated Blocking Voltage (V)	$R_{DS(ON)}$ (m $\Omega$ )	Maximum Continuous Current Rating	TO247-3L 	TO247-4L 	TO-263 / D2PAK 	Bare Chips
1200	350 m $\Omega$	6 A	GR350MT12D	GR350MT12K	GR350MT12J	
	160 m $\Omega$	20 A	GR160MT12D	GR160MT12K	GR160MT12J	
	75 m $\Omega$	36 A	GR75MT12D	GR75MT12K	GR75MT12J	GR75MT12-CAL
	40 m $\Omega$	62 A	GR40MT12D	GR40MT12K	GR40MT12J	
	30 m $\Omega$	80 A		GR30MT12K	GR30MT12J	GR30MT12-CAL
	20 m $\Omega$	92 A		GR20MT12K		GR20MT12-CAL
1700	1000 m $\Omega$	6 A	GR1000MT17D		GR1000MT17J	
	45 m $\Omega$	75 A		GR45MT17K		GR45MT17-CAL
	20 m $\Omega$	92 A		GR20MT17K		GR20MT17-CAL
3300	1000 m $\Omega$	1 A			GR1000MT33J	
	350 m $\Omega$	6 A			GR350MT33J	
						GR80MT33-



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# Conclusions

- **Well-rounded SiC MOSFET design that optimizes performance, robustness and reliability produced**
- **Design Parameters correlated with on-resistance, short circuit and avalanche characteristics**
- **GeneSiC ready to sample 3300 V/40 mOhm SiC MOSFETs to select US-based partners**
- **AEC-Q101 qualified parts available through Industry's leading distributors for**

# Thanks for Your Support!

